

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Hsu, *et al.*

Attorney Docket: TSM02-1205

Filed: Herewith

Examiner: TBD

Serial No.: TBD

Art Unit: TBD

For: Process for Improving Dielectric Properties in Low-k Organosilicate Dielectric Material

Mail Stop: Patent Application
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(a)

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Kristin Mattern

7/9/03
Date

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

The Applicant wishes to bring to the attention of the Patent and Trademark Office the information noted on the enclosed form PTO/SB/08A & 08B that may be considered material to the examination of the above-identified application.

No fee is due at this time, as this Information Disclosure Statement is being filed concurrently with the patent application.

Respectfully submitted,



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Substitute for form 1449/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>				Complete if Known	
				Application Number	TBD
				Filing Date	Herewith
				First Named Inventor	Hsu, et al.
				Art Unit	TBD
				Examiner Name	TBD
				Attorney Docket Number	TSM02-1205
Sheet	1	of	2		

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
		US-6,346,490 B1	02-12-2002	Catabay, et al.	
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FOREIGN PATENT DOCUMENTS						
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This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you are required to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P. O. Box 1450, Alexandria, VA 22313-1450.

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Substitute for form 1449B/PTO				Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Application Number	TBD
				Filing Date	Herewith
				First Named Inventor	Hsu, <i>et al.</i>
				Group Art Unit	TBD
				Examiner Name	TBD
				Attorney Docket Number	TSM02-1205
Sheet	2	of	2		

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite ¹ No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		Yang, S., <i>et al.</i> , "Processing and Characterization of Ultralow-Dielectric Constant Organosilicate," J. Vac. Sci. Technol. B, Vol. 19, No. 6 (Nov/Dec 2001) pp. 2155-2161.	
		Terry, J., <i>et al.</i> , "Alkyl-terminated Si(111) Surfaces: A High-Resolution, Core Level Photoelectron Spectroscopy Study," Journal of Applied Physics, Vol. 85, No. 1 (January 1, 1999) pp. 213-221.	
		Chang, T.C., <i>et al.</i> , "Eliminating Dielectric Degradation of Low-k Organosilicate Glass by Trimethylchlorosilane Treatment," J. Vac. Sci. Technol. B., Vol. 20, No. 4 (Jul/Aug 2002) pp. 1561-1566.	
		Chang, T.C., <i>et al.</i> , "Trimethylchlorosilane Treatment of Ultralow Dielectric Constant Material After Photoresist Removal Processing," Journal Of The Electrochemical Society, Vol. 149, No. 10 (August 2002) pp. F145-F148.	
		Mor, Y.S., <i>et al.</i> , "Effective Repair to Ultra-Low-k Dielectric Material (k~2.0) by Hexamethyldisilazane Treatment," J. Vac. Sci. Technol. B, Vol. 20, No. 4 (Jul/Aug 2002) pp. 1334-1338.	
		Chang, T.C., <i>et al.</i> , "Recovering Dielectric Loss of Low Dielectric Constant Organic Siloxane During the Photoresist Removal Process," Journal Of The Electrochemical Society, Vol. 149, No. 8 (June 2002) pp. F81-F84.	
		Liu, P., <i>et al.</i> , "Highly Reliable Chemical-Mechanical Polishing Process for Organic Low-k Methylsilsequioxane," J. Vac. Sci. Technol. B, Vol. 19, No. 4 (Jul/Aug 2001) pp. 1212-1218.	
		WOLF, S., "Silicon Processing for the VLSI Era," Vol. 4, Lattice Press, Sunset Beach, California (2002) pp. 639-670.	

Examiner Signature		Date Considered	
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